NC-6800 Non-contact measurement wafer sorting system (Belt drive transportation)

Selling Points

Non-contact measurement of resistivity, thickness and conductivity (P/N)
Number of cassette station can be changed by customers request
Eddy current method for resistivity, Electric capacitance method for wafer thickness
Temperature correction for silicon wafer function

Details

Applications

Semiconductor materials, Solar-cell materials (Silicon, Polysilicon, SiC etc)

Sample sizes

3 ~ 8 inch

Measuring range

[R] 1m ~ 200Ω·cm
[Thickness] 150 ~ 1200μm
*The range is separated from each Low, Middle, High and S-High probe type.
*Please refer the measurement range for each probe type as below;

①Low : 0.01~0.5Ω/sq (0.001~0.05Ω·cm)
②Middle : 0.5~10Ω/sq (0.05~0.5Ω·cm)
③High : 10~1000Ω/sq (0.5~60Ω·cm)
④S-High : 1000~3000Ω/sq (60~200Ω·cm)